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(71) Applicant: CYROS B.V. [NL/NL]; De Eiken 21, 7221 GJ STEENDEREN (NL).

(72) Inventor: SCHOOK, Robert; De Eiken 21, 7221 GJ STEENDEREN (NL).

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(54) Title: DEVICE AND METHOD FOR REGULATING PRESSURE

(57) Abstract: Device for regulating a pressure decrease in the flow direction of a fluid flow, comprising a chamber (3) provided with a tangential inlet (4) for having at least a first part of the fluid flow flow therethrough into the chamber, and with an outlet (5). A second part of the fluid flow in entering the chamber through second inlet 11. Tangential inlet (4) is connected to inflow openings (8) by channel (9). A vortex (6) is created in chamber (3) and liquid flow is reversed at the upper end of the chamber to flow axially back towards the outlet (5). The vortex provides for energy absorption which is distributed over the chamber and thus for a controlled and gradual pressure decrease. The pressure drop across the device is determined by the mutual ratio of first and second parts of the fluid flow, which ratio is determined by the flow resistance of first and second inlets (4, 11).

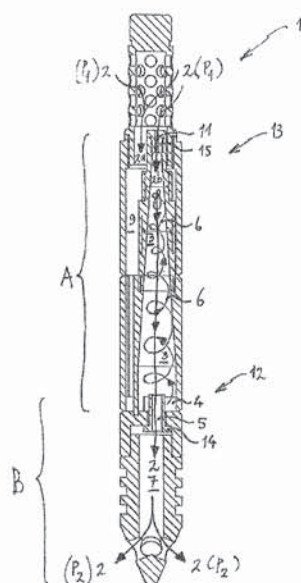


FIG. 1

